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	Application No.	Applicant(s)		
Notice of Allowability	10/615,048	BLATCHFORD, ET	AL.	
	Examiner	Art Unit		
	Sun J. Lin	2825		
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this apport or other appropriate communication GHTS. This application is subject to	olication. If not include will be mailed in due	ed course. THIS	
1. X This communication is responsive to Amendment & Remai	rks filed on 03/01/2005.			
2. The allowed claim(s) is/are 1-17.				
3. 🔀 The drawings filed on <u>08 July 2003</u> are accepted by the Ex	aminer.			
 4. Acknowledgment is made of a claim for foreign priority unall a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents 	been received. been received in Application No		tion from the	
International Bureau (PCT Rule 17.2(a)). * Certified copies not received:	cuments have been received in this r	iational stage applical		
Applicant has THREE MONTHS FROM THE "MAILING DATE" on noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	, ,	complying with the rec	uirements [†]	
5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give			OTICE OF	
 6. CORRECTED DRAWINGS (as "replacement sheets") mus (a) including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date 	on's Patent Drawing Review (PTO-9	ffice action of	·	
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the	, ,,	• ,	back) of	
7. DEPOSIT OF and/or INFORMATION about the depose attached Examiner's comment regarding REQUIREMENT I			lote the	
Attachment(s)				
1. Notice of References Cited (PTO-892)	5. Notice of Informal Pa	atent Application (PTC)-152)	
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Summary (Paper No./Mail Date	Mail Date		
 Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 				
4. Examiner's Comment Regarding Requirement for Deposit	8. X Examiner's Stateme	nt of Reasons for Allo	wance	
of Biological Material	9. Other			

Application/Control Number: 10/615,048

Art Unit: 2825

Reasons for Allowance

Claims 1 – 17 are allowed over the prior art of record. An examiner's statement of reasons for allowance is given in the following:

Claim 17 is allowed due to allowable subject matter as explained in the Office Action mailed to applicants on 12/02/2004.

Claims 1 – 16 are allowed because the prior art does not teach or fairly suggest the following subject matter:

- A method for generating an optical model, comprising generating lens aberration data according to wafer response to adjustment of a lens aberration of one or more lens aberrations of an initial lens, fitting one or more aberration functions to the lens aberration data to generate an optical model in combination with other limitations as recited in independent Claim 1;
- A system for generating an optical model, comprising a database operable to store lens aberration data associated with a wafer response to one or more lens aberrations of an initial lens; and a server coupled to the database and operable to generate lens aberration data according to the wafer response to adjustment of a lens aberration of the one or more lens aberrations, fit one or more aberration functions to the lens aberration data to generate an optical model in combination with other limitations as recited in independent Claim 6;
- A logic for generating an optical model, the logic embodied in a medium and operable to generate lens aberration data according to wafer response to adjustment of a lens aberration of one or more lens aberrations of an initial lens, fit one or more aberration functions to the lens aberration data to generate an optical model in combination with other limitations as recited in independent Claim 11;
- A system for generating an optical model, comprising means for generating lens aberration data according to wafer response to adjustment of a lens aberration of one or more lens aberrations of an initial lens, means for fitting one or more aberration functions to the lens aberration data to generate an optical model in combination with other limitations as recited in independent Claim 16.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably Art Unit: 2825

accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance".

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Sun J. Lin whose telephone number is (571) 272 – 1899. The examiner can normally be reached on Monday to Friday from 9:30am to 6:30pm.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-1782.

Sun J. Lin Patent Examiner Art Unit 2825 April 7, 2005 STACY A WHITHORE PRIMARY EXAMINER